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12110

Application Number

**Applicant(s)****Luc Ouellet et al.****Filing Date**

### Group Art Unit

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<p>T<sub>HM</sub></p>	<p>1) "New integrated optical multiplexer-demultiplexer realized on silicon substrate", S. Valette et al., pages 145-147.</p> <p>2) "Low-loss PECVD silica channel waveguides for optical communications", Eelectronics Letters, December 1990, Vol. 26, No. 25, pages 2135-2137.</p>
<p>T<sub>HM</sub></p>	<p>3) "Plasma-enhanced chemical vapor deposition of low-loss SiON optical waveguides at 1.5-um wavelength", Franco Bruno et al., Applied Optics, Vol. 30, No. 31, November 1991, pages 4560-4564.</p> <p>4) Rapid deposition of high-quality silicon-oxinitride waveguides", K. Kapser et al., IEEE Transactions Photonics Technology Letters, Vol. 3, No. 12, December 1991, pages 1096-1098.</p>

**EXAMINER**

**DATE CONSIDERED**

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

# INFORMATION DISCLOSURE CITATION

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Docket Number (Optional)	Application Number
1211	
Applicant(s)	
Luc Ouellet et al.	
Filing Date	Group Art Unit

*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
TAM	5) "Simple technologies for fabrication of low-loss silica waveguides", Q. Lai et al.
	6) "Formation of optical slab waveguides using thermal oxidation of SiO <sub>x</sub> ", Q. Lai et al., Electronics Letters, April 1993, Vol 29, No. 8, pages 714-716.
	7) "Hybrid optoelectronic digitally tunable receiver", Karen Liu et al., SPIE, Vol 2402, pages 104-114.
	8) "Single-Mode SiON/SiO <sub>2</sub> /Si optical waveguides prepared by plasma-enhanced chemical vapor deposition", Yuan-Kuang Tu et al., Fiber and Integrated Optics, Vol. 14, pages 113-139.
	9) "Low temperature, nitrogen doped waveguides on silicon with small core dimensions fabricated by PECVD/RIE", M. Hoffmann et al., pages 299-301.
	10) "Pure and fluorine-doped silica films deposited in a hollow cathode reactor for integrated optic applications", M.V. Bazylenko et al., J. Vac. Sci. Technol. A 14(2), Mar/Apr 1996, pages 336-345.
	11) "Optical properties of thin-film silicon-compatible materials", Daniel P. Poenar et al., Applied Optics, Vol. 36, No. 21, July 1997, pages 5122-5128.
	12) "Low-loss fiber-matched low-temperature PECVD waveguides with small-core dimensions for optical communications systems", Martin Hoffmann et al., IEEE Photonics Technology Letters, Vol. 9, No. 9, 1997, pages 1238-1240.
	13) "High quality low temperature DPECVD silicon dioxide", I. Pereyra et al., Journal of Non-Crystalline Solids, 1997, pages 225-231.
	14) A luminescence study of silicon-rich silica and rare-earth doped silicon-rich silica", A.J. Kenyon et al., Electrochemical Society Proceedings, Vol. 97-11, pages 304-318.
	15) "Thick SiO <sub>x</sub> N <sub>y</sub> and SiO <sub>2</sub> films obtained by PECVD technique at low temperatures", M.I. Alayo et al., Thin Solid Films 332, 1998, pages 40-45.
	16) "Deposition of thick TEOS PECVD silicon oxide layers for integrated optical waveguide applications", D.A.P. Bulla et al., Thin Solid Films 334, 1998, pages 60-64.
	17) "State of the art of integrated optics technology at LETI for achieving passive optical components", S. Valette, Journal of Modern Optics, 1998, Vol. 35, No. 6, pages 993-1005.
	18) "Simple method of fabricating polarisation-insensitive and very low crosstalk AWG grating devices", S.M. Ojha et al., Electronics Letters, January 1998, Vol. 34, No. 1, pages 78-79
	19) "Thermal annealing of waveguides formed by ion implantation of silica-on-Si", C.M. Johnson et al., Nuclear Instruments and Methods in Physics Research B, 141, 1998, pages 670-674.
	20) Silicon oxynitride planar waveguiding structures for application in optical communication", Rene M. de Ridder et al., IEEE Journal of Selected Topics in Quantum Electronics, Vol. 4, No. 6, 1988, pages 930-936.
	21) "Silicon-oxynitride layers for optical waveguide applications", R. Germann et al., Abstract No. 137.
	22) "Plasma enhanced chemical vapor deposition silicon oxynitride optimized for application in integrated optics", K. Worhoff et al., Sensors and Actuators, 74, 1999, pages 9-12
	23) "Wavelength tunable optical add-after-drop filter with flat passband for WDM networks", B.J. Offrein et al., IEEE Photonics Technology Letters, Vol. 11, No. 2, 1999, pages 239-241.
TAM	24) "High refractive index difference and low loss optical waveguide fabricated by low temperature processes", K. Imoto et al., Electronics Letters, 1993, Vol. 29, No. 12, pages 1123-1124.
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	6/30/03

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